

LIST OF REFERENCES BY APPLICANT	ATTY. DOCKET NO.	APPLICATION NO.
	B04-06	To Be Assigned
	APPLICANT	
	Michael J. Sullivan, <i>et al.</i>	
	FILING DATE	GROUP
	February 27, 2004	To Be Assigned


U.S. PATENT DOCUMENTS:

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
B	AA	6,561,928	05/03	Binette et al.	473	374	
	AB	6,325,730	12/01	Binette et al.	473	377	
	AC	6,315,684	11/01	Binette et al.	473	377	
	AD	6,315,681	11/01	Sullivan	473	373	
	AE	6,309,314	10/01	Sullivan, et al.	473	378	
	AF	6,299,550	10/01	Molitor et al.	473	354	
	AG	6,287,694	9/01	Zaleski et al.	428	402	
	AH	6,136,386	10/00	Nakahigashi et al.	427	536	
	AI	5,863,467	1/99	Mariner et al.	252	511	
	AJ	5,846,459	12/98	Mercuri	264	42	
	AK	5,330,680	7/94	Sakawaki et al.	252	309	
	AL	5,186,919	2/93	Bunnell	423	448	
	AM	4,961,988	10/90	Zhu	428	229	
	AN	4,895,713	1/90	Greinke et al.	423	448	
	AO	4,888,242	12/89	Matsuo et al.	428	408	
	AP	4,091,083	5/78	Hirschvogel et al.	423	415	
	AQ	3,625,896	12/71	Kirk et al.	252	62	
	AR	3,560,155	2/71	Olstowski et al.	23	209.2	
	AS	3,409,563	11/68	Olstowski et al.	252	506	
B	AT	3,404,031	10/68	Clayton et al.	117	201	


US PATENT PUBLICATIONS DOCUMENTS:

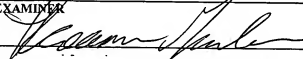
		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
B	AU	2003/0130061	07/03	Rajagopalan et al.	473	354	
B	AV	2003/0036597	02/03	Ide et al.	524	495	

FOREIGN PATENT DOCUMENTS:

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION Y N
	AW	WO 02/09823 A1	02/07/02	PCT			

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.):

	AX	Guo-Hua Chen, Da-Jun Wu, Wen-Gui Weng, and Wen-Li Yan; Dispersion of Graphite Nanosheets in a Polymer Matrix and the Conducting Property of the Nanocomposites; Polymer Engineering and Science, December 2001, Vol. 41, No. 12; Pages 2148, 2149, 2150, 2151, 2152, 2153, and 2154.
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EXAMINER 	DATE CONSIDERED 12-1-01
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>	